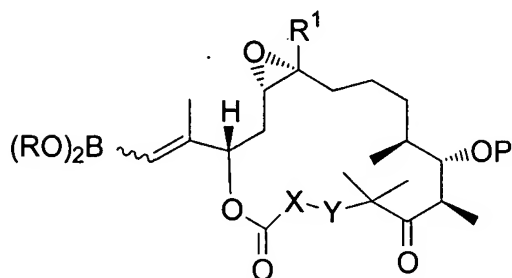


In the Claims:

Please cancel claims 1-17 without prejudice to their presentation in a continuing or divisional application.

Please add new claims 18 to 30:

18(new). A compound of formula:



wherein

R^1 is a H atom or a C_1 - to C_8 -alkyl group,

X-Y is a group of the formula $-\text{CH}_2\text{CH}(\text{OP})-$ or $-\text{CH}=\text{CH}-$,

P is a protecting group, and

each R is independently a C_1 - to C_8 -alkyl group or a C_2 - to C_6 -alkenyl group.

19(new). The compound of claim 18 wherein at least one R is a C_1 - to C_6 -alkyl group.

20(new). The compound of claim 18 wherein at least one R is a C_1 - to C_4 -alkyl group.

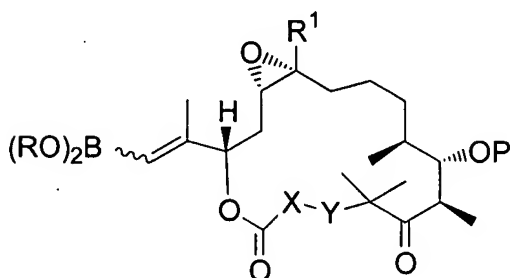
21(new). The compound of claim 18 wherein at least one R is a C_2 - to C_6 -alkenyl group.

22(new). The compound of claim 18 wherein at least one R is a C_2 - to C_4 -alkenyl group.

23(new). The compound of claim 18 wherein R^1 is a H atom or a C_1 - to C_6 -alkyl group.

24(new). The compound of claim 18 wherein R^1 is a H atom or a methyl group.

25(new). A process for preparing a compound of the formula



wherein

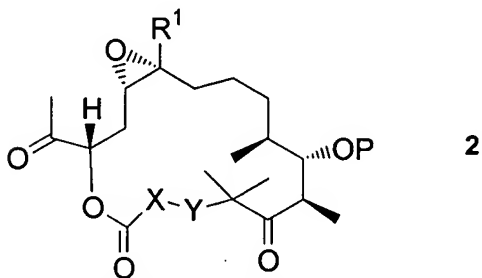
R^1 is a H atom or a C_1 - to C_8 -alkyl group,

X-Y is a group of the formula $-\text{CH}_2\text{CH}(\text{OP})-$ or $-\text{CH}=\text{CH}-$,

P is a protecting group, and

each R is independently a C_1 - to C_8 -alkyl group or a C_2 - to C_6 -alkenyl group;

comprising: reacting a compound of the formula 2:



with a compound of the formula $\text{HC}[\text{B}(\text{OR})_2]_3$.

26(new). The process according to claim 25 wherein the compound of the formula $\text{HC}[\text{B}(\text{OR})_2]_3$ is tris(ethylenedioxyboryl)methane.

27(new). The process according to claim 25 wherein the compound of the formula 2 and the compound of the formula $\text{HC}[\text{B}(\text{OR})_2]_3$ are reacted in the presence of a strong base.

28(new). The process according to claim 27 wherein the strong base is a C₁-C₄-alkyl lithium compound or a di-C₁-C₄-alkylamine lithium compound.

29(new). The process according to claim 28 wherein the strong base is butyllithium or dimethylamine lithium compound.

30(new). The process according to claim 25 wherein the compound of the formula II and the compound of the formula HC[B(OR)₂]₃ are reacted at a temperature of less than about -30°C.